Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	6	(mask or photomask or reticle) same glass near2 (blank or base or substrate) same (polish$3 or abra$4 or grind$3) same (colloid$2) near2 (silica or silicon dioxide or SiO".sub.2")	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 09:22
L2	0	(mask or photomask or reticle) same glass near2 (blank or base or substrate) same (polish$3 or abra$4 or grind$3) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2") not 1	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 09:23
L3	16	(mask or photomask or reticle) same glass same (blank or base or substrate) same (polish$3 or abra$4 or grind$3) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2") not 1 not 2	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 09:23
L4	2452	((mask or photomask or reticle) near3 (phase or shift$3 or reflect$3 or extreme ultraviolet or extreme UV or EUV) or PSM) same glass not 1 not 2 not 3	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 09:24
L5	86	4 and glass same (polish$3 or abra$4 or grind$3) same (silica or silicon dioxide or SiO".sub.2" or SiO$6)	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 09:25
L6	135	4 and glass same (polish$3 or abra$4 or grind$3) not 5	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 09:25
L7	7782	430/5.ccls.	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 09:27
L8	1848	7 and (mask or photomask or reticle) same glass same (blank or base or substrate) not 1 not 3 not 5 not 6	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 09:28
L9	655	4 and 7	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 09:28
L10	5	9 and (polish$3 or abra$4 or grind$3) same (silica or silicon dioxide or SiO".sub.2" or SiO$6) not 1 not 3 not 5 not 6	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 09:29

L11	8424	451/36,37,41,42,390.ccls. or 65/60.1,61.ccls. or 427/160,165,290,292.ccls.	US-PGPUB; USPAT; EPO; JPO; IBM_TDB.	ADJ	ON	2006/01/27 09:33
L12	579	11 and (colloid$2) same (silica or silicon dioxide or SiO".sub.2" or SiO$6) not 1 not 3 not 5 not 6 not 10	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 09:35
L13	489	12 and (polish$3 or abra$4 or grind$3) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2" or SiO$6)	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 09:36
L14	3	13 and hydroly$4 same (organosilicon or organo silicon or organic silicon or organic Si) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2" or SiO$6)	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 09:36
L15	415	13 and (polish$3 or abra$4 or grind$3) same (pressure or force or load) not 14	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 09:37
L16	54	15 and (pressure or force or load) same glass	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 09:38
L17	1375	51/308.ccls. not 1 not 3 not 5 not 6 not 10 not 14 not 16	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 09:40
L18	2	17 and hydroly$4 same (organosilicon or organo silicon or organic silicon or organic Si) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2" or SiO$6)	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 09:41
L19	3	17 and hydroly$4 same (organosilicon or organo silicon or organic silicon or organic Si) not 18	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 09:41
L20	70	17 and hydroly$4 with (silica or silicon dioxide or SiO".sub.2" or SiO$6) not 18 not 19	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 09:42
L21	5	20 and hydroly$4 same (silicon or Si) with (organic or polymer) not 18 not 19	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 09:43
L22	3	20 and hydroly$4 same (silicon or Si) same (organic or polymer) not 21	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 09:43

L23	12	(Kesahiro near2 Koike or Junji near2 Miyagaki).in. not 1 not 3 not 5 not 6 not 10 not 14 not 16 not 18 not 19 not 21 not 22	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 09:48
L24	1070	(polish$3 or abra$4 or grind$3) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2") same (alkali metal or sodium or potassium or "Na" or "K") not 1 not 3 not 5 not 6 not 10 not 14 not 16 not 18 not 19 not 21 not 22 not 23	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 09:54
L25	84	24 and 51/308.ccls. and (colloid$2) same (silica or silicon dioxide or SiO".sub.2") same (alkali metal or sodium or potassium or "Na" or "K")	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 09:51
L26	21	25 and (alkali metal or sodium or potassium or "Na" or "K") same impur$5	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 09:52
L27	4	(glass and (mask or photomask or reticle) and (blank or substrate) and (polish$3 or abra$4 or grind$3) and (colloid$2) and (silica or silicon dioxide or SiO".sub.2") and ("pH" or (protru$4 or bulg$3 or project$3 or bump$3))).clm. not 1 not 3 not 5 not 6 not 10 not 14 not 16 not 18 not 19 not 21 not 22 not 23 not 26	US-PGPUB; USPAT	ADJ	ON	2006/01/27 10:12
L28	774	430/4.ccls.	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 10:13
L29	1	(7 or 28) and (mask or photomask or reticle) same glass same (blank or substrate) same (polish$3 or abra$4 or grind$3) same ("pH" or (protru$4 or bulg$3 or project$3 or bump$3)) not 1 not 3 not 5 not 6 not 10 not 14 not 16 not 18 not 19 not 21 not 22 not 23 not 26 not 27	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 10:26
L30	5	(mask or photomask or reticle) same glass same (blank or substrate) same (polish$3 or abra$4 or grind$3) same "pH" not 1 not 3 not 5 not 6 not 10 not 14 not 16 not 18 not 19 not 21 not 22 not 23 not 26 not 27 not 29	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/01/27 10:31